

Docket No.: M4065.0239/P239

(PATENT)

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of:

Confirmation No.: 5354

Larry Hillyer et al

Application No.: 09/653,561

Allowed: July 21, 2006

Filed: August 31, 2000

Group Art Unit: 2812

For: METHOD AND MATERIAL FOR

REMOVING ETCH RESIDUE FROM HIGH ASPECT RATIO CONTACT

**SURFACES** 

Examiner: Alexander G Ghyka

## APPLICANT'S COMMENTS ON EXAMINER'S STATEMENT OF REASONS FOR ALLOWANCE

Commissioner for Patents Washington, DC 20231

Dear Sir:

Applicants agree in part with the Examiner's statement of reasons for allowance, contained in the Notice of Allowance mailed July 21, 2006 in that the prior art of record fails to disclose, teach or suggest the claimed invention. However, Applicants note that the Examiner's statement fails to address all limitations of all of the allowed claims. For example, certain claim limitations were not discussed in the Examiner's Reasons for Allowance, including those in most of the allowed claims, each of which defines a unique combination of features not shown or suggested by the prior art, providing additional reasons for allowance of each claim.

Furthermore, Applicants respectfully submits that the scope of the claimed invention should not be limited by the Examiner's statement, but rather the scope of the claimed invention should be based on the actual language of the al lowed claims.

Dated: August 22, 2006

Respectfully submitted,

Thomas J. D'Amico

Registration No.: 28,371 DICKSTEIN SHAPIRO LLP 1825 Eye Street, NW Washington, DC 20006

(202) 420-2232 Attorneys for Applicants